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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1-25 (canceled).

Claim 26 (currently a mended): A method of controlling the plasma flux distribution on a workpiece of an inductive plasma processor including a plasma excitation coil having a center axis and plural parallel connected windings adapted to be driven by an excitation source, the plural parallel connected windings being concentric with the axis so an exterior winding of the coil surrounds the remainder of the coil, the method comprising positioning the exterior winding relative to the remainder of the coil so the plasma density incident on the workpiece has a predetermined desired relationship;

the positioning step including turning the exterior winding and another winding of the coil relative to each other about the axis;

the exterior winding being turned relative to the another winding to assist in controlling azimuthal electric field distribution and azimuthal plasma density distribution of the processor; and

the method being performed on a plurality of different processors of the same

type having differing azimuthal electric field and plasma density distributions from

processor to processor and the exterior winding of each particular processor is turned

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relative to the remainder of the coil of the particular processor until tests indicate optimum uniform plasma distribution is achieved in each processor.

Claims 27-30 (canceled).

Claim 31 (currently amended): [[The]] A method of controlling the plasma flux distribution on a workpiece of an inductive plasma processor including a plasma excitation coll having a center axis and plural parallel connected windings adapted to be driven by an excitation source, the plural parallel connected windings being concentric with the axis so an exterior winding of the coil surrounds the remainder of the coil, the method comprising positioning the exterior winding relative to the remainder of the coil so the plasma density incident on the workpiece has a predetermined desired relationship, [[The]] elaim 26, wherein

the method is prefermed being performed on a plurality of different processors of the same type having differing azimuthal electric field and plasma density distributions from processor to processor and the exterior winding of each particular processor is moved relative to the remainder of the coil of the particular processor until tests indicate optimum uniform plasma distribution is achieved in each processor.